

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

Si Yi LI et al.

Application No.: 09/820,695

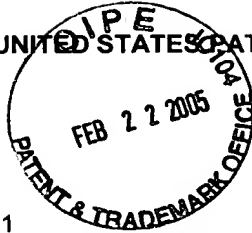
Filing Date: March 30, 2001

Title: METHOD OF PLASMA ETCHING LOW-K DIELECTRIC MATERIALS

Group Art Unit: 1763

Examiner: A. W. OLSEN

Confirmation No.: 4162



PETITION FOR EXTENSION OF TIME

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

The following extension of time is requested to: respond to the Official Action mailed October 5, 2004

two months to March 5, 2005 ☐ \$225.00 (2252) ☒ \$450.00 (1252)

- ☐ The shortened statutory period has been reset by an Advisory Action dated _____.
- ☒ An extension fee in the amount of \$ 450.00 is enclosed.
- ☐ Charge _____ to Deposit Account No. 02-4800.
- ☐ Charge _____ to credit card. Form PTO-2038 is attached.

The Director is hereby authorized to charge any appropriate fees under 37 C.F.R. §§1.16, 1.17 and 1.21 that may be required by this paper, and to credit any overpayment, to Deposit Account No. 02-4800. This paper is submitted in duplicate.

Respectfully submitted,

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